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ABSTRACT



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A reticle (16) having a test pattern (TP)
for measurement of an optical characteristic of a
5 projection optical system (17) has a pattern adapted
so that a high frequency component of a spectrum at
a pupil plane (18) of the projection optical system
(17) is reduced or suppressed. Illumination light is
projected to the test pattern of the reticle (16) in
10 one direction or plural directions, and positions of
images of the test pattern (TP), formed by the
projections in the plural directions, are detected and,
based on it, the optical characteristic of the
projection optical system (17) is measured.

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